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**ABSTRACT OF THE DISCLOSURE**

A method of depositing a metal or other desired material onto a substrate using a gas generated via the sublimation of solid material precursors, wherein a solid precursor is introduced into a liquid in a bubbler apparatus so that the bubbler then contains vapors of solid precursor, and then sweeping a carrier gas through the bubbler to a reactor containing a substrate which is coated with the precursor via chemical vapor deposition.

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